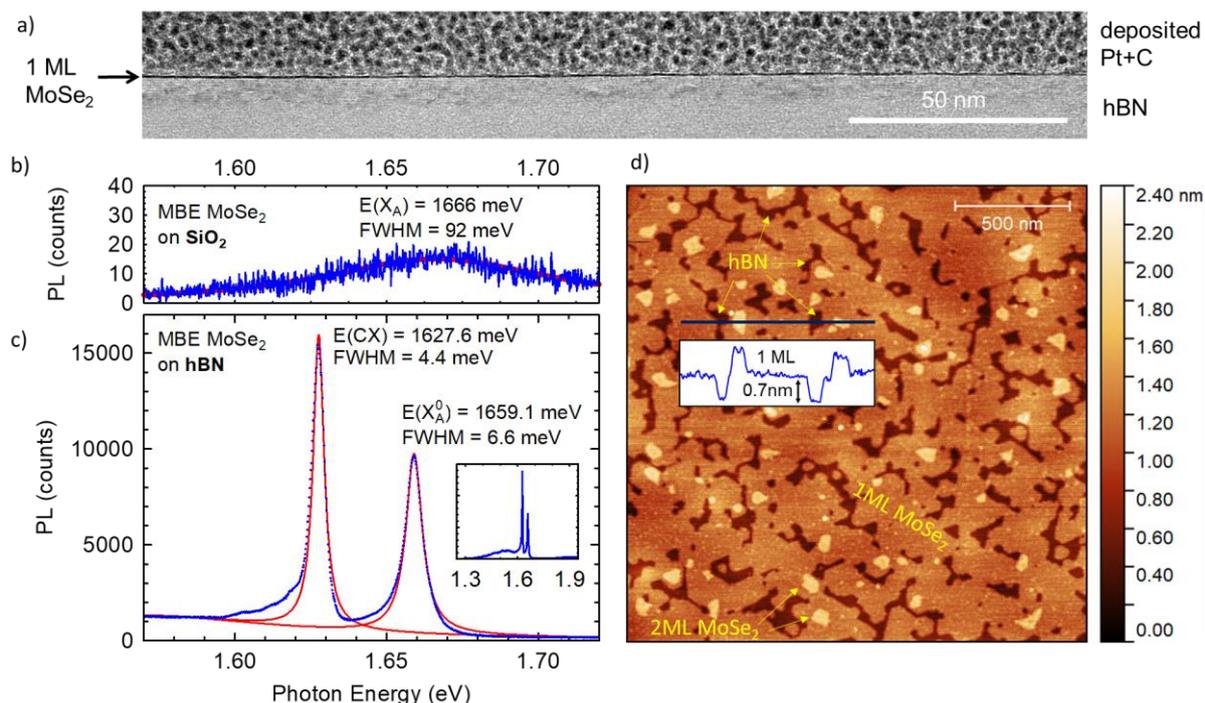
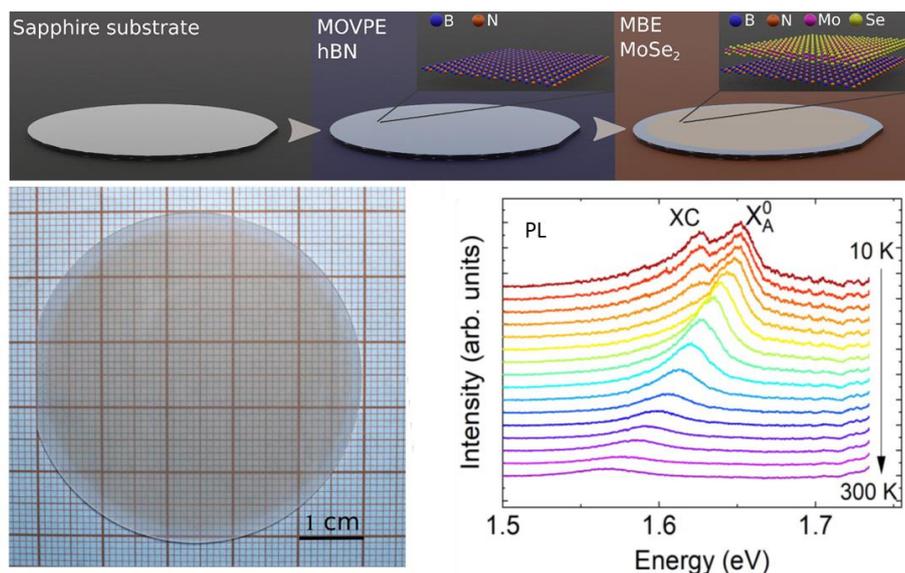


## Supplemental File related to PCSI-48 talk: MBE Growth of Transition-Metal Dichalcogenides

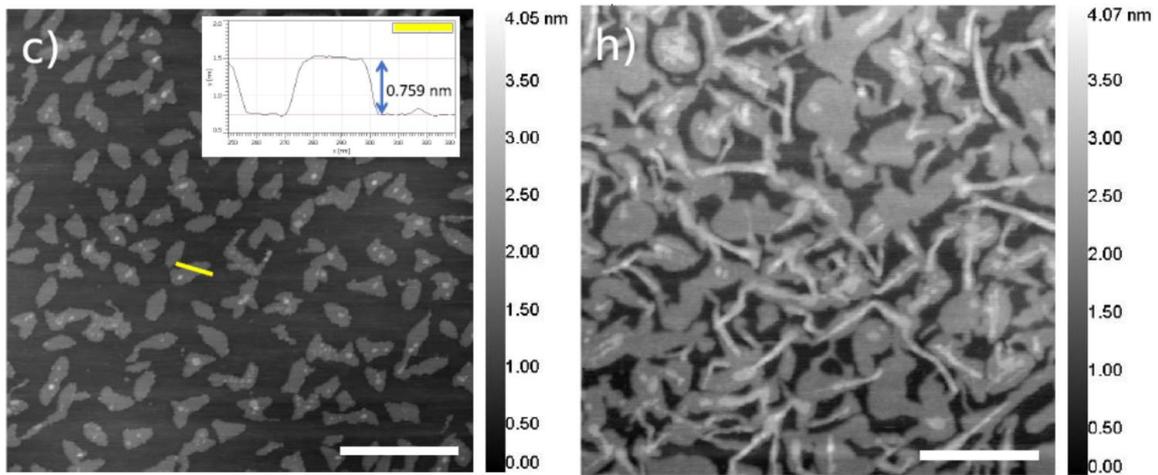
Wojciech Pacuski, University of Warsaw, Poland



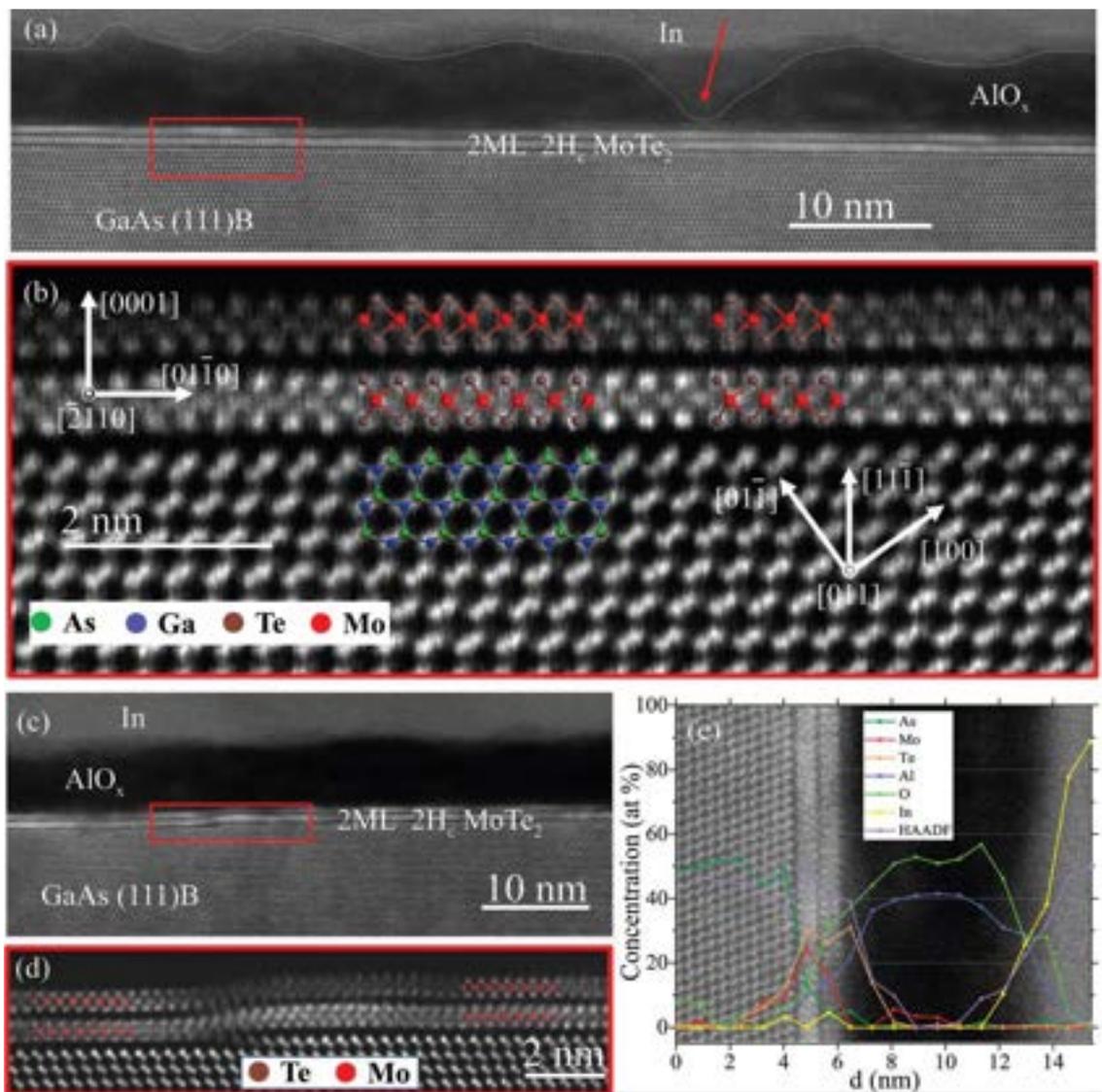
**Fig. 1. Narrow excitonic lines presented for the first time for MBE-grown TMD.** TEM cross-section of studied MoSe<sub>2</sub> monolayer grown on exfoliated hBN is shown in (a). Low temperature ( $T = 10$  K) PL spectra (blue curves) of MBE MoSe<sub>2</sub> grown on SiO<sub>2</sub> (b) and hBN (c) both produced in the same growth process. Only for MoSe<sub>2</sub> grown on hBN it is possible to resolve neutral exciton line  $X_{A0}$  and charged exciton line CX. Red curves show Lorentzian fits with following parameters: 1659.1 meV energy and 6.6 meV FWHM for the neutral exciton of MoSe<sub>2</sub> grown on hBN; 1627.6 meV energy and 4.4 meV fwhm for the charged exciton of MoSe<sub>2</sub> grown on hBN; and 1666 meV energy and 92 meV FWHM of MoSe<sub>2</sub> grown on SiO<sub>2</sub>. Insert in (c) shows PL spectrum in wider spectral range. (d) AFM image of the sample shown in (a,c), with the almost complete monolayer, only in a very small part covered by the second layer. Size of the scanned area is  $2 \mu\text{m} \times 2 \mu\text{m}$ . The inset shows the height profile with 1 ML and 2 ML of MoSe<sub>2</sub> and uncovered hBN. [W. Pacuski et al., Nano Letters 20, 3058 (2020).]



**Fig. 2. Scheme of production of wafer with MBE MoSe<sub>2</sub> monolayer on hBN buffer and sapphire substrate.** Low temperature photoluminescence spectra shows resolved charged exciton and neutral exciton lines. [K. Ludwiczak et al., ACS Appl. Mater. Interfaces 13, 47904 (2021).]



**Fig. 3.** Examples of MoTe<sub>2</sub> grains grown by MBE on hBN substrate. At lower temperatures flat 1 ML thick grains are grown, while at higher temperatures 2D grains are associated with 1D structures identified as Mo<sub>5</sub>Te<sub>6</sub>. The scale bar corresponds to 500 nm. [B. Seredyński et al., J. Cryst. Growth 596, 126806 (2022).]



**Fig. 4.** HR TEM image of MoTe<sub>2</sub> bilayer grown on GaAs (111)B by MBE, subsequently protected in vacuum by Al, which transforms in air to AlO<sub>x</sub> final protection layer. Cross-section is made for area of indium contact prepared for electron transport investigations. [Z. Ogorzałek et al., Nanoscale 12, 16535 (2020).]